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PATENT
30205/37456

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application of: Geun Su Lee et al.)	I hereby certify that this paper and the
)	documents referred to as enclosed
Serial No.: 09/884,313)	therewith are being deposited with the
)	United States Postal Service as first class
Filed: June 19, 2001)	mail, postage prepaid, on August 7, 2003,
)	in an envelope addressed to
For: Photoresist Polymer for Top-)	Commissioner for Patents, P.O. Box
Surface Imaging Process by Silylation)	1450, Alexandria, Virginia 22313-1450
and Photoresist Composition)	
Containing the Same)	
)	
Group Art Unit: 1752)	Michael R. Hull
)	Reg. No. 35,902
Examiner: Yvette C. Thornton)	Attorney for Applicants

1752

AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, Virginia 22313-1450

Sir:

In response to the office action mailed on May 19, 2003, please amend the
above-identified patent application as follows: